

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): Stephen W. Bedell, et al.

Examiner: Unassigned

Serial No.: To be assigned

Art Unit: Unassigned

Filed: Herewith

Docket: YOR920030203US1 (16694)

For: FORMATION OF A SILICON
GERMANIUM-ON-INSULATOR STRUCTURE
BY OXIDATION OF A BURIED POROUS SILICON LAYER

Dated: September 12, 2003

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

PRELIMINARY AMENDMENT

Sir:

In connection with filing the above-identified application under 37 C.F.R.

§1.53(b), applicants submit the following amendments and remarks for consideration by the Examiner and entry of record in the above-identified patent application.

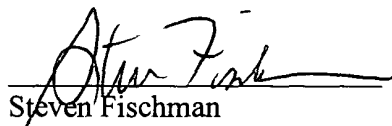
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Dated: September 12, 2003


Steven Fischman